

### **REMARKS**

Claims 1-5 are pending in the above-identified application, and were rejected. Claims 6-20 were withdrawn from consideration. With this Amendment, claim 1 was amended. Accordingly, claims 1-5 remain at issue.

#### **I. 35 U.S.C. § 102 Anticipation Rejection of Claims**

Claims 1-2 and 4-5 were rejected under 35 U.S.C. § 102(b) as being anticipated by Abe (U.S. Patent No. 6,521,920). Applicant respectfully traverses this rejection.

Claim 1 is directed to a method for manufacturing a solid-state imaging device, and includes the step of forming a channel stop section comprising a plurality of impurity regions adjoining each other on the side of the photosensor in the substrate by multiple times of ion implantation with multiple implanting energies.

Abe discloses a solid state image sensor. In Abe, secondary p-type channel stop region 44 is formed in the portion below the primary p-type channel stop region 32. (See col. 5, lines 16-21 and Figure 1.) Abe does not disclose or suggest forming a channel stop section comprising a plurality of impurity regions adjoining each other, as required by claim 1. Accordingly, claim 1, and claims 2 and 4-5 that depend from claim 1, are allowable over Abe, and Applicant respectfully requests withdrawal of this rejection.

#### **II. 35 U.S.C. § 103 Obviousness Rejection of Claims**

Claim 3 was rejected under 35 U.S.C. § 103(a) as being unpatentable over Abe in combination with Alvis, et al. (U.S. Patent No. 6,455,385). Applicant respectfully traverses this rejection.


As discussed above, Abe does not disclose or suggest forming a channel stop section comprising a plurality of impurity regions adjoining each other, as required by claim 1. Thus it would not have been obvious to one of ordinary skill in the art to combine the teachings of Abe and Alvis, et al. to derive claim 3. Accordingly, Applicant respectfully requests withdrawal of this rejection.

**III. Conclusion**

In view of the above amendments and remarks, Applicant submits that all claims are clearly allowable over the cited prior art, and respectfully requests early and favorable notification to that effect.

Respectfully submitted,

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